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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/616,914		07/11/2003	Toshiji Taiji	8017-1094	2404
466	7590	07/24/2006		EXAM	INER
YOUNG &	THOM	SON	UMEZ ERONINI. LYNETTE T		
745 SOUTH 2ND FLOOR		REET	ART UNIT	PAPER NUMBER	
ARLINGTON, VA 22202				1765	
				DATE MAILED: 07/24/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/616,914	TAIJI ET AL.				
Office Action Summary	Examiner	Art Unit				
	Lynette T. Umez-Eronini	1765				
The MAILING DATE of this communication Period for Reply	appears on the cover sheet wit	h the correspondence address				
A SHORTENED STATUTORY PERIOD FOR RE WHICHEVER IS LONGER, FROM THE MAILING - Extensions of time may be available under the provisions of 37 CF after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period for reply within the set or extended period for reply will, by stany reply received by the Office later than three months after the mearned patent term adjustment. See 37 CFR 1.704(b).	G DATE OF THIS COMMUNIC R 1.136(a). In no event, however, may a re riod will apply and will expire SIX (6) MONT atute, cause the application to become ABA	ATION. ply be timely filed THS from the mailing date of this communication. ANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 1	1 May 2006.					
,	<i>,</i> —					
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice unde	er <i>Ex parte Quayle</i> , 1935 C.D.	11, 453 O.G. 213.				
Disposition of Claims						
4) ⊠ Claim(s) 1 and 4-6 is/are pending in the appear 4a) Of the above claim(s) is/are without 5) □ Claim(s) is/are allowed. 6) ⊠ Claim(s) 1 and 4-6 is/are rejected. 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction an	drawn from consideration.					
Application Papers						
9) The specification is objected to by the Exam 10) The drawing(s) filed on is/are: a) a Applicant may not request that any objection to the Replacement drawing sheet(s) including the constant. The oath or declaration is objected to by the	accepted or b) objected to be the drawing(s) be held in abeyand rection is required if the drawing(s	ce. See 37 CFR 1.85(a). s) is objected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for fore a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the p application from the International Bur * See the attached detailed Office action for a line	ents have been received. ents have been received in Ap priority documents have been reau (PCT Rule 17.2(a)).	plication No eceived in this National Stage				
Attachment(s) 1) Notice of References Cited (PTO-892)	∆ □ 1-4 •	(DTO 442)				
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date						
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/ Paper No(s)/Mail Date	(08) 5) Notice of Info	ormal Patent Application (PTO-152) -				

DETAILED ACTION

This communication is in response to Applicants' Remarks in Amendment (filed 5/11/2006), which was persuasive in showing Kaisaki (US 6,109,317 B1) failed to teach the specific combination of a slurry comprising silica, an oxidizing agent, a benzotriazole-based compound, a diketone, which is selected from the group of 1,2-, 1,3- and 1,4-diketones, and water. Hence, a new Office Action is presented.

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

3. Claims 1 and 4-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kaisaki et al. (US 6,194,317 B1).

Kaisaki discloses, "The working liquid aids processing in combination with the abrasive article through chemical mechanical polishing process" (column 12, lines 49-51) and ". . . the working liquid is an aqueous solution which includes . . . an oxidizing material or agent" (column 12, lines 54-58). Kaisaki discloses the working liquid comprises: additional chelators that include 1,3-diketones (column 14, lines 13-14), corrosion inhibitor such as benzotriazole (column 14, line 63 - column 15, line 2 and column 15, lines 39-47), and inorganic particulates that include silica (column 22-24). The aforementioned reads on,

A slurry for chemical mechanical polishing, which comprises a silica polishing material, an oxidizing agent, a benzotriazole-based compound, a diketone and water, and wherein said diketone is at least one the of a compound selected from the group consisting of 1,2-diketones, 1,3-diketones and 1,4-diketones, in claim 1.

It is noted that Kaisaki differs in failing to disclose Applicants' specific combination of silica, oxidizing agent, benzotriazole, diketone and water.

However, it would have been obvious to one having ordinary skill in the art at the time the invention was made to select any combination of components of the polishing slurry as taught by Kaisaki, including Applicants' claimed polishing components, for the purpose removing a second material from the surface of a first material under the action of an abrasive article (column 8, lines 14-18).

Kaisaki discloses, "buffers may be added to the working liquid to control the pH.... In addition, the most preferred buffers can be adjusted to span the pH range from acid to near-neutral... (column 14, lines 40-50), which encompasses and reads on, a slurry for chemical mechanical polishing wherein a value of a pH is in a range of 1 to 7, in claim 4.

Kaisaki differs in failing to disclose a content weight ratio of said diketone to said benzotriazole-based compound is not less than 0.05 but not greater than 50 and not less than 0.05 but not greater than 10, respectively in claims 1 and 6.

However, Kaisaki illustrates the specific combination of a benzotriazole and diketone is known. As a result, it would have been obvious to one of ordinary skill in the art at the time the invention was made to select any weight content of benzotriazole and diketone, including Applicants' specifically claimed weight ratio of diketone/benzotriazole-based compound that would effectively accomplish the disclosed composition in the absence of evidence of unexpected results.

Response to Arguments

4. Applicant's arguments, see Remarks, filed 5/11/2006, with respect to the rejection(s) of claim(s)s 1, 5, and 5 under 35 U.S. C. 102(b) have been fully considered and are persuasive. Therefore, the rejection has been withdrawn. However, upon further consideration, a new ground(s) of rejection is made in view of Kaisaki (US 6,194,317 B1) under 35 U.S.C. 103(a).

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lynette T. Umez-Eronini whose telephone number is 571-272-1470. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Art Unit 1765

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July 10, 2006

NADINE NORTON SUPERVISORY MATERI EXAMINER ART UNIT 1765

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